Boeckl

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[54]	[54] SPIN COATING PROCESS FOR PREVENTION OF EDGE BUILDUP		
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[58]	Field of Search		
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57] ABSTRACT

A spin coating process produces a constant film thickness across a planar substrate by placing a frame around the substrate boundary to act as an auxiliary surface to allow a continuous film of the fluid to be spin coated. The auxiliary surface is elevated with respect to the plane of the substrate surface.

8 Claims, 4 Drawing Figures

